


AZ 300 MIF Developer

Product	AZ 300 MIF Developer
Manufacturer	EMD Performance Materials Corp
Composition	>95% water, <3% tetramethylammonium hydroxide; liquid
Synonyms	
Typical Uses	Developer for photolithography
Hazards	 200 Corrosive to metals CATEGORY 1 , Skin corrosion/irritation CATEGORY 2 , Serious eye damage/eye irritation CATEGORY 2A , Acute toxicity CATEGORY 4 (oral)
Storage	Cabinet 13 (bases cabinet in Wet Aisle 1); underneath litho wet decks
Disposal	Pour into wet deck (Litho Wet Deck 1/2, Wet Deck 1A/1B/2A) and rinse copiously with DI water.
Comments	Login to tool <i>Litho Wet Deck #1 - TMAH</i> or <i>Litho Wet Deck #2 - TMAH</i> when using. Wear PPE when handling: chemical-resistant gloves, acid apron, face shield.
Status	



Check First

Please contact a nanoFAB staff member for uses not listed above.